

	Hits	Search Text	DBs
23	2	((substrate or wafer or workpiece or platen) near16 (barrier or protective ARC or antireflect\$4 or BARC or poly\$3phenol\$4)) same (resist or photoresist or photosensitive or photocur\$3 or (radiation near9 sensitive)), same (plat\$4 or electroplat\$4)) and (adhes\$4 near26 polyphenol\$4 near22 polymer\$4 near19 monomer\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	3	((substrate or wafer or workpiece or platen) near16 (barrier or protective ARC or antireflect\$4 or BARC or poly\$3phenol\$4)) same (resist or photoresist or photosensitive or photocur\$3 or (radiation near9 sensitive))) and (adhes\$4 near26 polyphenol\$4 near22 polymer\$4 near19 monomer\$4) and (plat\$4 or electro\$4plat\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
25	3	((substrate or wafer or workpiece or platen) near16 (barrier or protective ARC or antireflect\$4 or BARC or poly\$3phenol\$4)) same (resist or photoresist or photosensitive or photocur\$3 or (radiation near9 sensitive))) and (adhes\$4 same (polyphenol\$4 near22 polymer\$4 near19 monomer\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
26	3	((substrate or wafer or workpiece or platen) near16 (barrier or protective ARC or antireflect\$4 or BARC or poly\$3phenol\$4)) same (resist or photoresist or photosensitive or photocur\$3 or (radiation near9 sensitive))) and (adhes\$4 same (polyphenol\$4 near22 polymer\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
27	2	((substrate or wafer or workpiece or platen) near16 (barrier or protective ARC or antireflect\$4 or BARC or poly\$3phenol\$4)) same (resist or photoresist or photosensitive or photocur\$3 or (radiation near9 sensitive))) and (adhes\$4 same (polyphenol\$4 near22 polymer\$4))	US-PGPUB